

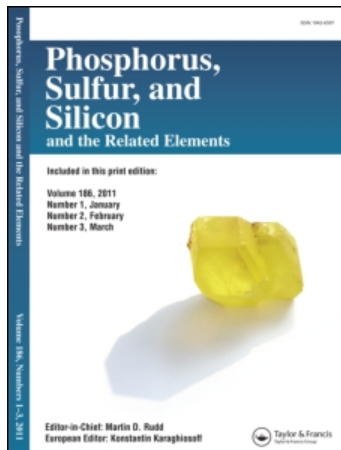
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FORMATION OF THE FREE ION OF FLUORENONE RADICAL ANION IN TETRAHYDROFURAN BY THE FLASH PHOTOLYSIS OF THE SULFONYL CARBANIONS

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FORMATION OF THE FREE ION OF FLUORENONE RADICAL ANION IN TETRAHYDROFURAN BY THE FLASH PHOTOLYSIS OF THE SULFONYL CARBANIONS

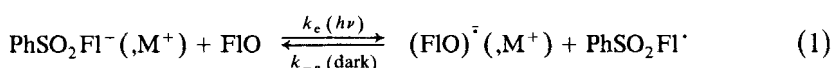
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The free ion of fluorenone radical anion ($\text{FIO})^{\cdot -}$ was formed even in tetrahydrofuran (THF) by the flash photolysis of the alkali-metal salts of the sulfonyl carbanion in the presence of neutral FIO and this was attributed to the ion pair structure of the sulfonyl carbanions.

Studies of back-electron-transfer reactions in the dark with a rate constant of k_{-e} such as reaction (1) induced by flash



photolysis¹ of the solution containing the alkali-metal salt of the carbanion and neutral aromatic ketone give us information about ion-pair structures of the reactant and the product ions. We report here the interesting behavior of the alkali-metal fluorenyl carbanions substituted in the 9-position with a phenylsulfonyl group (see Figure 1; abbreviated as $\text{PhSO}_2\text{Fl}^-(\text{M}^+)$ (contact ion pair) and PhSO_2Fl^- (free ion), and $\text{PhSO}_2\text{Fl}^-(\text{M}^+)$ in reaction (1) represents collectively both the carbanions).² As can be seen from Figure 2 and Table I, the direct reduction of neutral fluorenone (FIO) by alkali metal in the absence of $\text{PhSO}_2\text{Fl}^-(\text{M}^+)$ in THF or hexamethylphosphoric triamide (HMPA) yields the contact $(\text{FIO})^{\cdot -}(\text{M}^+)$ ion pair³ or the free $(\text{FIO})^{\cdot -}$ ion, respectively, as expected by the nature of the solvents used. Although the absorption maximum (λ_{max}) of the free $(\text{FIO})^{\cdot -}$ ion observed at 570 nm has not been reported, there is no ambiguity about the formation of monomeric free $(\text{FIO})^{\cdot -}$ ion;⁴ in diluted HMPA solution, it is not necessary to consider an entity other than the free ion. On the other hand, the alkali-metal fluorenone radical anions in ethereal solvents have been studied,⁵⁻⁷ particularly by Hirota *et al.*,⁵ in detail by means of esr and electronic absorption spectroscopies; according to their assignments, the absorption peaks around 530 nm can be attributed to the monomeric contact $(\text{FIO})^{\cdot -}(\text{M}^+)$ ion pair and/or triple ion, although great complexity results from the coexistence of the radical triple ion as well as the ion quadruplet.⁵

As depicted in Figure 3, photo-ejection of an electron from the $\text{PhSO}_2\text{Fl}^-(\text{M}^+)$ ion pairs (10^{-4} – 10^{-5} M) in the presence of excess neutral FIO (10^{-3} M) in THF gives two absorption peaks; one can be attributed to the contact $(\text{FIO})^{\cdot -}(\text{M}^+)$ ion pair and the other to free $(\text{FIO})^{\cdot -}$ ion by the fact that the spectra are in full accord with the λ_{max} s which appeared in the directly reduced solutions.⁸ Coinciding in behavior with many alkali-metal salts of carbanions⁹ and radical anions, the position of the λ_{max}

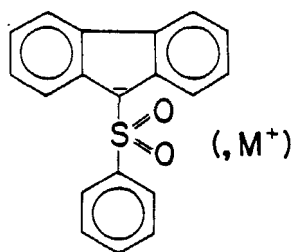


FIGURE 1 Alkali-metal salts of fluorenyl carbanions substituted in the 9-position with a phenylsulfonyl group, $\text{PhSO}_2\text{Fl}^-(\text{M}^+)$, in which (M^+) represents collectively the contact and the solvent-separated ion pairs and the free ion.

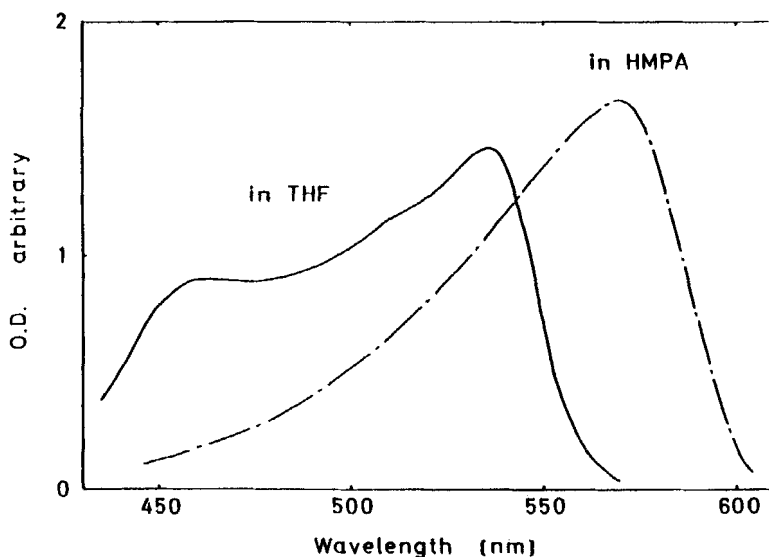


FIGURE 2 Electronic absorption spectra of fluorenone radical anions formed by direct reduction of neutral FIO with potassium metal at 23°C.

of the contact ion pairs formed by flash photolysis was shifted, depending upon the counter alkali-metal cation, and that of the free ions was not altered (see Table I).

It is interesting to note that even in the THF solution of $\text{PhSO}_2\text{Fl}^-\text{K}^+$ containing potassium tetraphenylboride (KBPh_4 , 5×10^{-3} M), the absorption peak attributable to the free $(\text{FIO})^-$ ion also appears as a result of photo-ejection, although the ratio of optical densities $\text{OD}_{570}/\text{OD}_{535}$ decreased from 0.77 to 0.50. In the solvent mixture consisting of THF and HMPA (23 vol%), the λ_{max} attributable to the contact $(\text{FIO})^-\text{K}^+$ ion pair was shifted from 535 in THF to 545 nm and a similar shift was observed upon the addition of 18-crown-6 (7×10^{-3} M) to THF (545 and 570 nm; the latter is due to the free $(\text{FIO})^-$ ion), suggesting that in these mixed solvents the contact ion pairs are converted into externally solvated contact ion pairs¹⁰ by the HMPA or crown compounds.

TABLE I

Absorption peaks produced by flash photolysis of the solutions containing PhSO_2Fl^- (M^+) and neutral FlO^a at 23°C

Counter cation, M^+	Solvent	Absorption maxima (nm)		
		Contact (FlO^-), M^+	Externally solvated contact (FlO^-), M^+ , S	Free (FlO^-)
Li^+	THF	525	—	570
Na^+	THF	530	—	570
K^+	THF	535	—	570
K^+	THF- KBPh_4^b	535	—	570
Li^+	THF-HMPA	—	535	570
Na^+	THF-HMPA	—	538	570
K^+	THF-HMPA	—	545	570
K^+	THF-crown ^c	—	545	570
K^+	HMPA	—	—	570
K^+	THF ^{d, e}	535	—	—
K^+	HMPA ^d	—	—	570

^a Concentrations of the carbanions; 10^{-4} – 10^{-5} .

^b Potassium tetraphenylboride (4.8×10^{-3} M).

^c 18-Crown-6 (6.8×10^{-3} M).

^d Direct reduction of FlO with potassium metal.

^e Absorption peaks other than that listed herein also appeared.

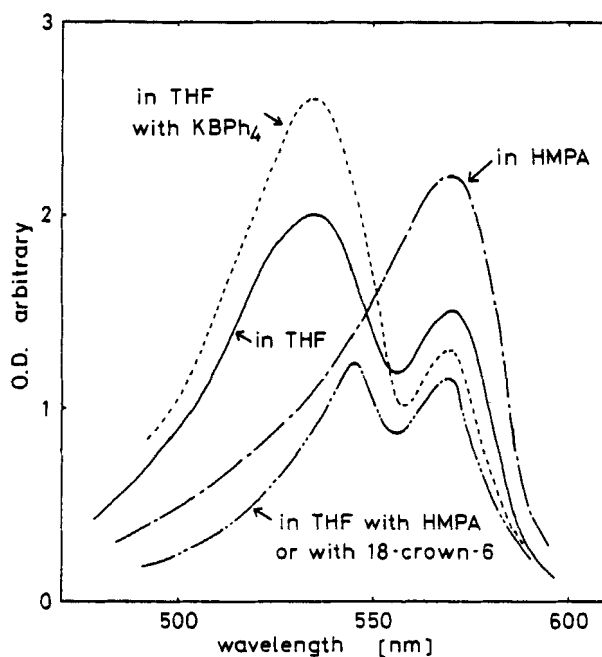


FIGURE 3 Transient absorption spectra obtained by flash photolysis of the sulfonyl carbanions PhSO_2Fl^- (M^+) in the presence of neutral fluorenone in THF and HMPA (40 μsec after flash). O.D.'s of the absorption bands: 0.12 in THF with KBPh_4 at 535 nm; 0.25 in THF at 535 nm; 0.3 in HMPA at 570 nm; 0.08 in THF with HMPA or with 18-crown-6 at 545 nm.

TABLE II
Decay rate constants of fluorenone radical anions (23°C)

Carbanion	k_{-e}/ϵ (cm s ⁻¹) in THF ^a		k_{-e} (M ⁻¹ s ⁻¹) in HMPA
	Contact (FIO) ⁻ , M ⁺	Free (FIO) ⁻	Free (FIO) ⁻
PhSO ₂ Fl ⁻ , Li ⁺	4.1×10^5	5.3×10^5	
PhSO ₂ Fl ⁻ , Na ⁺	4.6×10^5	6.4×10^5	
PhSO ₂ Fl ⁻ , K ⁺	4.9×10^5	8.7×10^5	1.3×10^9

^a ϵ is molar extinction coefficient of fluorenone radical anions.

From the flash photolyses of the sulfenyl carbanion PhSFl⁻(K⁺) and the sulfinyl carbanion PhSOFl⁻, K⁺¹¹ in the presence of neutral FIO in THF, only the contact (FIO)⁻, K⁺ ion pair was formed. Therefore, the formation of the free (FIO)⁻ radical anion in THF should be attributable to the characteristics of the sulfonyl carbanions; the alkali-metal cation of the sulfonyl carbanion is located at the sulfonyl moiety which is partially negatively charged owing to an intramolecular charge-transfer interaction between the negative center and the neighboring sulfonyl group² and to the inductive effect of the S—O bonds; these tend to prevent the cation from moving toward the (FIO)⁻.

The back-electron-transfer reactions from the alkali-metal fluorenone radical anions to PhSO₂Fl⁻ are clearly shown by the state of the ion-pair structure of the fluorenone radical anions formed. Decay of the radical anions with a rate constant k_{-e}/ϵ obeyed second-order kinetics up to ca. 80% conversion and was faster from the free (FIO)⁻ than from the contact (FIO)⁻, M⁺ ion pairs in THF (see Table II). The rate constant for the back electron transfer in HMPA was determined in the form of k_{-e} since the molar extinction coefficient of the free (FIO)⁻ in HMPA was determined.⁴

In conclusion, the free (FIO)⁻ radical anion was formed even in THF by flash photolysis of the sulfonyl carbanions and this results from the ion-pair structure of the sulfonyl carbanions.

REFERENCES AND NOTES

- Flash photolysis apparatus and kinetic spectroscopy used in this experiment was described in ref. 2.
- S. Nishi and M. Matsuda, *J. Am. Chem. Soc.*, **101**, 4632 (1979).
- Absorption peaks other than that responsible for the monomeric contact (FIO)⁻, M⁺ ion pair appeared, but in the present study our interest was focused on the formation of both the monomeric contact (FIO)⁻, M⁺ ion pair and the free (FIO)⁻ radical anion.
- Molar extinction coefficient of the free (FIO)⁻ radical anion was determined to be 7.4×10^3 M⁻¹ cm⁻¹ in HMPA by measuring the optical densities before and after electron transfer from anthracene radical anion to neutral FIO. ESR spectrum of the free (FIO)⁻ radical anion in HMPA gives g value (2.0038) and hyperfine splitting constants for the free (FIO)⁻ radical anion (1.73 ± 0.01 (H_{1,8}); 0.12 ± 0.005 (H_{2,7}); 2.29 ± 0.02 (H_{3,6}); 0.63 ± 0.005 (H_{4,5}) gauss). No alkali-metal splitting was observed.
- S. W. Mao, K. Nakamura and N. Hirota, *J. Am. Chem. Soc.*, **96**, 5341 (1974).
- T. Shida, S. Iwata and M. Imamura, *J. Phys. Chem.*, **78**, 741 (1974).
- A. G. Evans, J. C. Evans, P. J. Emes and S. I. Haider, *J. Chem. Soc. Perkin 2*, 1121 (1974).

8. The photochemistry of the sulfonyl carbanion could contribute to the observed results; the $(\text{FIO})^{\cdot-}$ formed by our xenon flash photolysis may correspond to *ca.* 10 mol % of the $\text{PhSO}_2\text{Fl}^-(\text{M}^+)$ existing in the ground state. Therefore, the concentration of the $\text{PhSO}_2\text{Fl}^-(\text{M}^+)^*$ in the excited state may be greater than 10 mol % of the sulfonyl carbanion in the ground state. In general, the ratio of the solvent-separated ion pair in the excited state to that in the ground state becomes progressively greater as the ion pair is excited (e.g., T. E. Hogen-Esch and J. Plodinec, *J. Am. Chem. Soc.*, **100**, 7633 (1978)). Therefore, the formation of the free $(\text{FIO})^{\cdot-}$ from the sulfonyl carbanion may be attributable to the characteristic ion-pair structure of the sulfonyl carbanions (see ref. 2 and the text).
9. T. E. Hogen-Esch and J. Smid, *J. Am. Chem. Soc.*, **87**, 669 (1965); **88**, 307, 318 (1966).
10. L. L. Chan, K. H. Wong and J. Smid, *J. Am. Chem. Soc.*, **92**, 1955 (1970).
11. The alkali-metal salts of sulfenyl carbanions $\text{PhSFl}^-(\text{M}^+)$ exist as a mixture of the contact and the solvent-separated ion pairs at room temperature.²